

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Accompanying Continuation Application under
37 CFR 1.53(b):

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Prior Application: N. HASEGAWA et al
Serial No. 08/904,754
Filed: August 1, 1997

Group Art Unit: 1752
Examiner: S. Rosasco
For: PHOTOMASK AND PATTERN FORMING METHOD
EMPLOYING THE SAME

PRELIMINARY AMENDMENT

Assistant Commissioner of Patents
Washington, D.C. 20231

November 10, 1998

Sir:

Prior to examination, please amend the above application
as follows.

IN THE SPECIFICATION

Please amend the specification as set forth below.

Page 1, line 11, change "size" to --sizes--;

line 17, change "one of" to --a--; and

line 18, change "portions on" to --portion on one
of--.

Page 2, line 9, change "a little quantity of" to --some
of the--;

line 10, change "is" to --are--;

line 22, change "is" to --are--; and

line 27, delete "an" (second occurrence).

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